

CLAIMS

1. A silver alloy for use in a reflective film, comprising silver as a main element and at least one rare-earth element as a first dopant element.
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2. The silver alloy for use in a reflective film according to claim 1, wherein the first dopant element is at least either dysprosium or thulium. .
3. The silver alloy for use in a reflective film according to claim 1, wherein
10 the first dopant element is at least any one of terbium, gadolinium, erbium, neodymium, holmium, praseodymium, samarium, lanthanum, cerium, ytterbium, and europium.
4. The silver alloy for use in a reflective film according to any one of
15 claims 1 to 3, comprising gallium as a second dopant element.
5. The silver alloy for use in a reflective film according to any one of claims 1 to 3, comprising as the second dopant element at least either platinum or palladium.
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6. The silver alloy for use in a reflective film according to any one of claims 1 to 3, comprising as the second dopant element at least one element selected from magnesium, zinc, nickel, molybdenum, gold and aluminum.
- 25 7. The silver alloy for use in a reflective film according to any one of claims 1 to 3, comprising as the second dopant element at least one element selected from copper, cobalt, tin, titanium, bismuth, manganese, scandium, and yttrium.

8. The silver alloy for use in a reflective film according to any one of claims 1 to 3, comprising as the second dopant element at least one element selected from silicon, chromium, iron, zirconium, niobium, tantalum, tungsten, rhodium, iridium, indium, lead, calcium, antimony, strontium, hafnium, germanium, and boron.

9. The silver alloy for use in a reflective film according to any one of claims 1 to 8, wherein a total of the concentration of the first dopant element and the concentration of the second dopant element are 0.01 to 5.0 atomic %.

10. The silver alloy for use in a reflective film according to claim 9, wherein the total of the concentration of the first dopant element and the concentration of the second dopant element are 0.01 to 3.0 atomic %.

11. A sputtering target, comprising the silver alloy as defined in any one of claims 1 to 10.